16. (twice amended) The method of claim 1 wherein the resin comprises a polymer than contains phenolic units.

17. (twice amended) The method of claim 1 wherein the resin comprises a polymer that contains phenolic and photoacid-labile alkyl acrylate units.

18. (twice amended) The method of claim 1 wherein the resin comprises a polymer that contains 1) phenolic units, 2) phenyl units, and 3) photoacid-labile alkyl acrylate units.

**REMARKS**

Claims 1, 2 and 16-18 have been amended. No new matter has been added by virtue of that amendments.

Claims 1-3 and 7-19 were rejected under 35 U.S.C. 102(e) over Chen et al. (U.S. Patent 6103447). As the rejection is understood, the Chen document is cited for a range of a component (b) of 0.005 to about 10 wt. %. The rejection is traversed.

Respectfully, the Chen document is clearly insufficient to sustain the instant rejection.

Indeed, the Chen document in no manner provides a sufficient disclosure, or otherwise directs the skilled worker to Applicants' claimed invention.

For instance, **all the examples of Chen** report imaging with *248 nm radiation* and have photoacid generator compounds present at *less* than 5 weight %.

Indeed, the entire thrust of Chen is to a composition that has a blend of resins with differing acid labile groups. See Chen at column 2, lines 48-52.

In view thereof, reconsideration and withdrawal of the rejection are requested.

Claims 1-3 and 11-18 were rejected under 35 U.S.C. 102(e) over Barclay et al. (U.S. Patent 6,492,086).

While Applicants fully disagree with the rejection, claim 1 (the only pending independent claim) has been amended to recite that the one or more photoacid generator compounds are present in a concentration of at least 5 weight percent based on weight of total solids of the photoresist composition.

The Barclay document is cited for a composition containing a solid ratio of 4.72 of di-t-butyl phenyl iodonium camphorsulfonate. See page 4, first paragraph of the Office Action.

It is believed that citation does not represent a Section 102 disclosure of Applicants' claimed invention. Accordingly, the rejection should be withdrawn. See, for instance, *In re Marshall*, 198 USPQ at 346 ("[r]ejections under 35 USC 102 are proper only when the claimed subject matter is identically disclosed or described in the prior art.").

It is believed the application is in condition for immediate allowance, which action is earnestly solicited.

Respectfully submitted,

Peter F. Corless (Reg. 33,860)
EDWARDS & ANGELL, LLP
P.O. Box 9169
Boston, MA 02209
(617) 439-4444

## MARKED VERSION TO SHOW CHANGES

1. (twice amended) A method for forming a photoresist relief image on a substrate comprising:

(a) applying a coating layer of a chemically-amplified positive photoresist composition on a substrate, the photoresist composition comprising a resin and one or mre photoacid generating compounds, wherein the one or more photoacid generator compounds are present in a concentration of at least [about] 5 weight percent based on weight of total solids of the photoresist composition;

(b) exposing the photoresist coating layer to EUV radiation.

2. (twice amended) The method of claim 1 wherein the photoresist composition comprising a phenolic resin that comprises at least three distinct repeat units [A method for forming a photoresist relief image on a substrate comprising:

(a) applying a coating layer of a chemically-amplified positive photoresist composition on a substrate, the photoresist composition comprising a phenolic resin and one or more photoacid generating compounds, the resin comprising at least three distinct repeat units;

(b) exposing the photoresist layer to EUV radiation having a wavelength of less than about 160 nm, or electron beam or ion beam radiation].

16. (twice amended) The method of claim 1 [or 2] wherein the resin comprises a polymer than contains phenolic units.

17. (twice amended) The method of claim 1 [or 2] wherein the resin comprises a polymer that contains phenolic and photoacid-labile alkyl acrylate units.

18. (twice amended) The method of claim 1 [or 2] wherein the resin comprises a polymer that contains 1) phenolic units, 2) phenyl units, and 3) photoacid-labile alkyl acrylate units.